

**What is claimed is:**

1. A protective film of a plasma display panel, comprising a main component of magnesium oxide (MgO) and  
5 an addition of silicon (Si) less than 500ppm.

2. The protective film as claimed in claim 1, wherein a content of the added silicon is preferably about 20ppm to 300ppm.

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3. The protective film as claimed in claim 1, wherein the protective film further includes an addition of calcium (Ca) less than 50ppm, iron (Fe) less than 50ppm, aluminum (Al) less than 250ppm, nickel (Ni) less than 5ppm, sodium (Na) less than 5ppm and potassium (K) less than 5ppm.  
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4. The protective film as claimed in claim 1, wherein a discharge gas containing xenon (Xe) more than 5% is sealed within the plasma display panel.

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5. A method of fabricating a protective film of a plasma display panel, comprising the step of:

forming the protective film having a main component of magnesium oxide (MgO) and an addition of silicon (Si)  
25 less than 500ppm.

6. The method as claimed in claim 5, wherein the protective film is formed on the plasma display panel by a vacuum deposition process.

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7. The method as claimed in claim 5, wherein the protective film is formed on the plasma display panel by any one process of a chemical vapor deposition (CVD), a E-

beam process, an ion-plating and a sputtering.

8. The method as claimed in claim 5, wherein a content of the added silicon is preferably about 20ppm to 300ppm.

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9. The method as claimed in claim 5, wherein the protective film further includes an addition of calcium (Ca) less than 50ppm, iron (Fe) less than 50ppm, aluminum (Al) less than 250ppm, nickel (Ni) less than 5ppm, sodium (Na) less than 5ppm and potassium (K) less than 5ppm.

10. The method as claimed in claim 5, further comprising the step of:

15 sealing a discharge gas containing xenon (Xe) more than 5% within the plasma display panel.